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Aims & Scope

See also http://www.elsevier.com/locate/jphotochem

JPPA publishes Notes, Short Communications and Full-length Articles on chemical phenomena induced by interactions between light and molecules/matter, of all kinds. Organic, inorganic, biological, macromolecular, supramolecular integrated systems; semiconductor and metallic systems are all included, and the widest range of photochemistry disciplines is covered.

The scope includes studies of a broad range of processes in photochemistry such as energy, electron and proton transfer; quantum yield determinations and measurements of rate constants for primary and secondary photochemical processes; studies on steady-state and time-resolved emission; absorption and scattering spectroscopy applied to photochemistry; mechanistic investigation of photochemical reaction; and identification of the products of photochemical reactions.

Topical areas covered by the journal include fundamental studies of condensed phase, gas phase and atmospheric photochemistry, synchrotron radiation chemistry and spin effects on photochemical processes. Reports on emerging areas like: solar energy conversion, environmental remediation, and related photocatalytic reactions are also welcome. In addition investigations of molecules in intense laser fields such as reactive intermediates; nonlinear photochemical behaviour; and ultra-fast relaxation (femtosecond laser research applied to photochemistry) are published. Furthermore, reports of studies employing microscopy in spectroscopy and photochemistry; single-molecule photochemistry and spectroscopy; nano-scale photochemical phenomena and laser micro/nano-processing are welcome as long as the work contributes not only to photochemical applications but also to a basic understanding of molecular characteristics. JPPA also welcomes manuscripts on timeresolved X-Ray diffraction for probing photoinduced structural changes in chemical and biological reactions. Papers relating to polymerization, photodegradation or photostabilization of polymers, chemical aspects of phototherapy and the design of photoreactors will also be considered.

Prospective authors of review articles are kindly advised to consult the Journal of Photochemistry and Photobiology C: Photochemistry Reviews and follow manuscript preparation instructions as described at http://www.elsevier.com/locate/jphotochemrev.

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